

ABSTRACT

Provided is a vacuum processing apparatus having a stage which is arranged to be capable of deviating a phase of a to-be-processed substrate without giving rise to a positional deviation thereof.

A vacuum processing apparatus (SM) of this invention having a stage (4) on which is disposed the to-be-processed substrate (Sw) further has a lifting/rotation mechanism (Rm) capable of lifting the to-be-processed substrate lying on the stage off from an upper surface of the stage to a predetermined height position so that, at this lifted position, the to-be-processed substrate is capable of rotation about a substrate center by a predetermined rotational angle. The lifting/rotation mechanism has: a driving rod (5) built into the stage so as to be moveable up and down and also be rotatable; and a substrate supporting body (6) having a base end plate part (61) capable of contacting a central region, including the substrate center, of the to-be-processed substrate. The substrate supporting body (6) further has at least two arm plate parts (62) elongated from the base end plate part outward thereof so as to be capable of contacting such a portion of the to-be-processed substrate as is lying diametrically. The substrate supporting body is ordinarily immersed into the stage so that the to-be-processed substrate is supported by such base end plate part and arm plate parts as are lifted by an upward movement of the driving rod.